



AF IHW

**TRANSMITTAL LETTER  
(General - Patent Pending)**

Docket No.  
SEC.910

In Re: Application Of: **Kyoung-Hwan CHIN et al.**

Application No. <b>09/988,302</b>	Filing Date <b>November 19, 2001</b>	Examiner <b>Gentle WINTER</b>	Customer No.	Group Art Unit <b>1746</b>	Confirmation No. <b>8429</b>
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Title: **CLEANING APPARATUS OF A HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION CHAMBER  
AND CLEANING METHOD THEREOF**

COMMISSIONER FOR PATENTS:

Transmitted herewith is:

**Combined Request for Withdrawal of Finality of Office Action and Amendment Under 35 C.F.R. 1.116**

in the above identified application.

- ☒ No additional fee is required.
- ☐ A check in the amount of \_\_\_\_\_ is attached.
- ☒ The Director is hereby authorized to charge and credit Deposit Account No. **50-0238** as described below.
  - ☐ Charge the amount of \_\_\_\_\_
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*Signature*

Dated: **10 September 2004**

**ADAM C. VOLENTINE  
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I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to the "Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450" [37 CFR 1.8(a)] o.  
(Date)

*Signature of Person Mailing Correspondence*

*Typed or Printed Name of Person Mailing Correspondence*

CC:



Serial No. 09/988,302  
SEC.910  
Amendment dated 10 September 2004

**THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re PATENT APPLICATION of:

Kyoung-Hwan CHIN et al.

Group Art Unit: 1746

Serial No.: 09/988,302

Examiner: Gentle WINTER

Filed: 19 November 2001

CLEANING APPARATUS OF A  
HIGH DENSITY PLASMA  
CHEMICAL VAPOR DEPOSITION  
CHAMBER AND CLEANING  
METHOD THEREOF

**COMBINED REQUEST FOR WITHDRAWAL OF  
FINALITY OF OFFICE ACTION AND  
AMENDMENT UNDER 35 C.F.R. § 1.116**

U.S. Patent and Trademark Office  
220 20th Street S.  
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Arlington, VA 22202

Sir:

In response to the Office Action dated 13 July 2004, the period for response to which extends through 13 October 2004, Applicants respectfully traverse the “finality” of the Office Action. Applicants also respectfully request that the above-identified patent application be amended as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 5 of this paper.